

Multiple Star



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PRODUCT INFORMATION

Vaksis Multiple Star platform is composed of many vacuum chambers. This platform has a linear cluster structure and involves the techniques and combinations below:

CONFIGURATION MATRIX

Techniques	Magnetron Sputtering (MS)	Thermal Evaporation (Th E)	Electron Beam (e-Beam)	Organic and Metal Evaporation (OLED/OPV)	Plasma Enhanced CVD (PE-CVD)	Multi Tech.
Multiple Star	✓	✓	✓	✓	✓	MS, Th E, e-Beam, OLED/OPV, PE-CVD ICP, PE-CVD CCP

TECHNICAL SPECIFICATIONS

Ultimate Vacuum Pressure $\leq 5 \times 10^{-8}$ Torr
Number of Chambers up to 5
Substrate Size 4"- 8" diameter
Substrate Heating max. 400°C
Substrate Rotation 3-30 rpm
Cooling Where necessary
Loading With Load Lock and Transfer Chamber
Control Fully Automatic
Additional Gas Safety Available Upon Request

POWER SOURCES

- DC and/or RF Power Supply for Sputtering Magnetron Source
- Effusion Cell A.C. Power Supply for Metal and/or Organic Evaporation Sources
- High-Current Low-Voltage A.C. Power Supply for Resistive Thermal Evaporation Source
- Power Supply for Electron Beam Evaporation Source
- DC and/or RF Power Supply for Capacitively coupled plasma (CCP) and RF Power Supply for Inductively coupled plasma (ICP) Sources

SOFTWARE

System operation by user-friendly software. It is not only the automation and control software but also coating management software which allows the user design his/her specific coating experiments, examine the process parameters used in the past, and use the recipes/coatings developed in the past without hustle. Human and machine safeties are prime importance in the operations performed by the software. A graphical user interface will allow the user to see the status of the system during operation.

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